## PATENT APPLICATION

JUL 2 9 2004

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

the Application of

hunichi SEKI et al.

Group Art Unit: 1762

Application No.: 09/701,534

Examiner:

M. Cleveland

Filed: November 30, 2000

Docket No.: 107291

For:

METHOD FOR FORMING SILICON FILM AND INK COMPOSITION FOR INK JET

## INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

Pursuant to 37 CFR §1.56, the attention of the Patent and Trademark Office is hereby directed to the references listed on the attached PTO-1449. Unless otherwise indicated herein, one copy of each reference is attached. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the references be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

- $\boxtimes$ This Information Disclosure Statement is being filed before the mailing date of a first Office Action on the merits after the filing of a Request for Continued Examination under 37 CFR §1.114. No certification or fee is required.
- $\boxtimes$ 2. English-language Abstracts of the non-English language references are attached.
- $\boxtimes$ 3. Computer-generated English translations of the Japanese Patent Publications for references 3 and 5 have been obtained from the website of the Japanese Patent Office ([http://www.jpo.go.jp]), and are attached, but have not been reviewed for accuracy.
- $\boxtimes$ Reference 5 was forwarded by an Information Disclosure Statement filed November 30, 2000. However, a translation was not provided at that time as such was not reasonably available.

Respectfully submitted,

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Date: July 29, 2004

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DEPOSIT ACCOUNT USE **AUTHORIZATION** Please grant any extension necessary for entry; Charge any fee due to our Deposit Account No. 15-0461 JUL 2 9 2004 W

Sheet 1 of 1
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Form PTO-1449 (REV. 8-83)	× d	US Dept. of Commerce PATENT & TRADEMARK OFFICE	ATTY DOCKET NO. 107291			APPLICATION NO. 09/701,534			
INFORMATION DISCLOSURE STATEMENT									
(Use several sheets if necessary)			APPLICANT(S) Shunichi SEKI et al.						
			FILING DATE November 30, 2000			GROUP 1762			
		U.S. PAT	ENT DO	CUMENTS					
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	DATE NAME			CLASS	SUB CLASS	
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		FOREIGN P.	DOCUMENTS			1			
		DOCUMENT NUMBER		DATE	COUNTRY		CLASS	SUB CLASS	
	1	GB 2 077 710 A		12/23/1981	Great Britain				
	2	JP-A 64-029661 w/ Abstract		01/31/1989	Japan				
	3	JP-A 09-237927 w/ Abstract and translatio	n	09/09/1997	Japan				
	4	JP-A 63-111454 w/ Abstract		05/16/1988	Japan				
	5	JP-A 10-321536 w/ Abstract and translatio	n	12/04/1998	Japan				
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)									
	6	"Advances in deposition Processes for Pass	sivation I	Films", W. Kern et	al., J. Vac. Sci. Techi	nology,	14, 1082, ©	1977.	
	7	"Substitutional doping of Amorphous Silicon", W. E. Spear et al., Solid State Communications, 17, 1193, @1975.							
			1000						
EXAMINER					DATE CO	DATE CONSIDERED			
Examiner: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.									

Date: July 29, 2004